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/D.W./	YOUNG-BAE PARK ET AL: "EFFECT OF HYDROGEN PLASMA PRECLEANING ON THE REMOVAL OF INTERFACIALAMORPHOUS LAYER IN THE CHEMICAL VAPOR DEPOSITION OF MICROCRYSTALLINE SILICON FILMS ON SILICON OXIDE SURFACE" APPLIED PHYSICS LETTERS, AMERICAN INSTITUTE OF PHYSICS. NEW YORK, US, vol. 68, no. 16, 15 April 1996 (1996-04-15), pages 2219-2221, XP000585161 ISSN: 0003-6951 page 2219

DATE CONSIDERED 03/23/2009

Y&T August 8, 2005